

TSMC-99-646B



July 17, 2001

#3/98/98107
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To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

Subject:

Serial No. 09/846,536 05/02/01

Wen-Ting Chu, Hsin-Ming Chen

A NOVEL SELF-ALIGNED, LOW CONTACT
RESISTANCE, VIA FABRICATION PROCESS

Grp. Art Unit: 2811

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 5,834,369 to Murakami et al., "Method of
Preventing Diffusion Between Interconnect and Plug", discloses
a method for a Al line over an W-plug.

U.S. Patent 5,994,213 to Wang et al., "Aluminum Plug
Process", teaches an Al plug process.

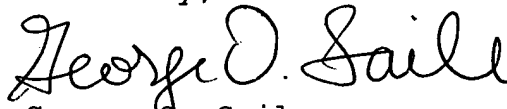
RECEIVED
JUL 20 2001
TC 2800 MAIL ROOM

U.S. Patent 5,956,609 to Lee et al., "Method for Reducing Stress and Improving Step-Coverage of Tungsten Interconnects and Plugs", discusses a plug/line process.

U.S. Patent 5,472,912 to Miller, "Method of Making an Integrated Circuit Structure by Using a Non-Conductive Plug", discloses a non-conductive plug that partially fills the via hole.

U.S. Patent 5,913,143 to Harakawa, "Method of Making a MultiLayer Interconnection of Semiconductor Device Using Plug", discusses an inter-level insulating film formed on a first Al film and a contact hole formed to partly expose the first Al film.

Sincerely,

A handwritten signature in cursive script that reads "George O. Saile".

George O. Saile,
Reg. No. 19572

09/846,536

Wen-Ting Cha et al.

05/02/01

2810

(Use several sheets if necessary)

U. S. PATENT DOCUMENTS

CZ30 MAIL ROOM

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FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Portrains Pages, Etc.)

A large, stylized, handwritten letter 'Z' is drawn on a piece of white paper with horizontal blue lines. The letter is formed by a single continuous black line. It starts with a horizontal top bar, followed by a diagonal stroke down to the left, and ends with a horizontal bottom bar. The letter is positioned in the center of the page.

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11/15/01

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through